

<b>Notice of References Cited</b>	Application/Control No. 10/544,783	Applicant(s)/Patent Under Reexamination TERASHIMA ET AL.	
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#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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	C	US-			
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#### FOREIGN PATENT DOCUMENTS

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#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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	V	D. Mangelick et al., "Formation of Ni silicide from Ni(Au) films on (111)Si" April, 15th 1996, Journal of Applied Physics, Vol. 79 Issue 8, Pages 4078-4086.
	W	B. Bokhonov et al., "In-situ investigation of the formation of nickel silicides during interaction of single-crystalline and amorphous silicon with nickel" April, 26th 2001, Journal of Alloys and Compounds, Vol. 319, Pages 187-1195.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.